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Electron Mean-Free-Path Dependence of the Vortex Surface Impedance

Mattia Checchin

Performance Frontier Group, SRF Section, TD



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Trapped flux surface resistance

$$R_s(T, B) = R_{BCS}(T) + \boxed{R_{fl}(B)} + R_0$$

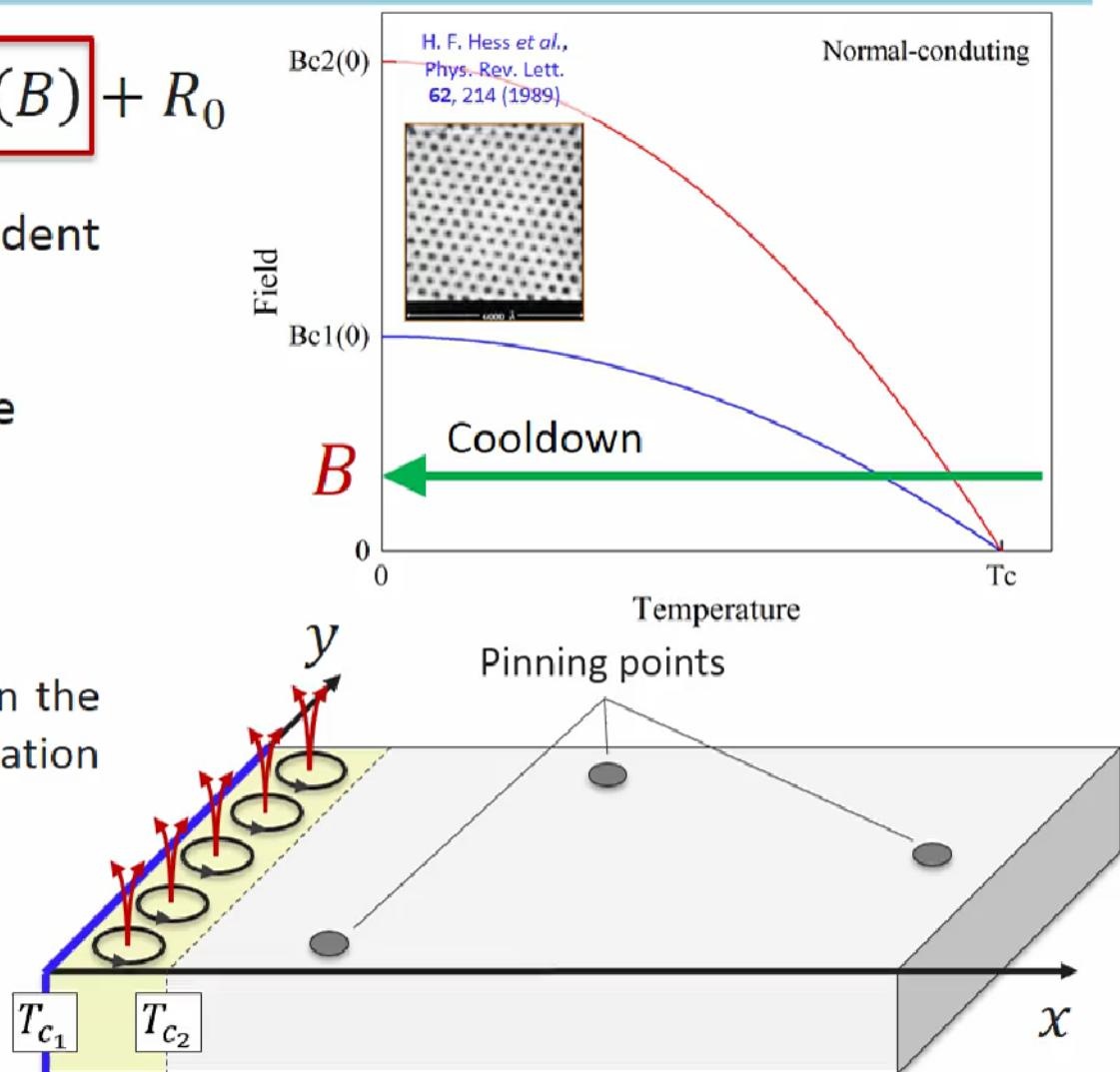
$R_{BCS} \Rightarrow$ temperature-dependent part of the surface resistance

$R_0 \Rightarrow$ intrinsic residual resistance

$R_{fl} = \eta_t S B \Rightarrow$ trapped flux

surface resistance:

- If pinned, vortices may survive in the Meissner state introducing dissipation
- η_t —flux trapping efficiency
- S —trapped flux sensitivity
- B —external magnetic field



Flux Trapping Efficiency

— η_t —

Thermodynamic force during cooldown

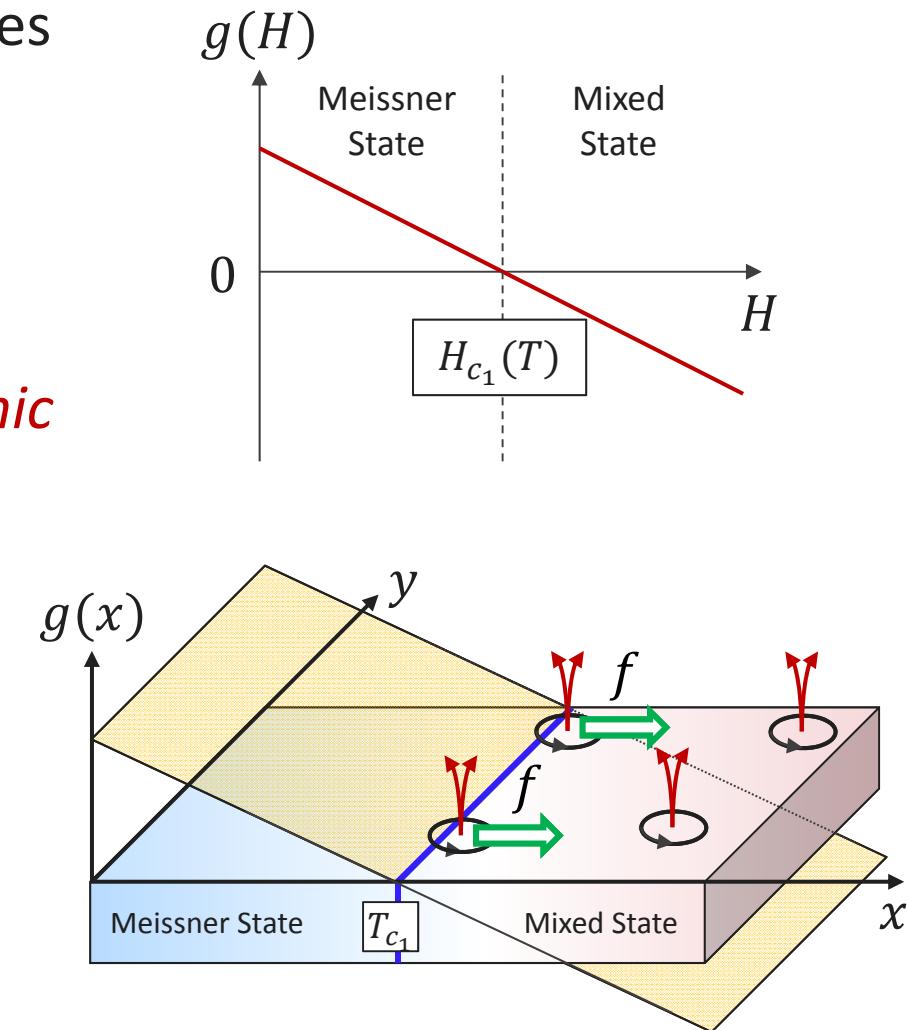
The Gibbs free energy density defines the stability of vortices in the SC:

$$g = B(H_{c_1}(T) - H)$$

We can define the *thermodynamic force* acting on the vortex as:

$$f = -\frac{\partial g}{\partial x} = -\frac{\partial g}{\partial T} \frac{\partial T}{\partial x}$$

$$f = \frac{2BH_{c_1}(0)T}{T_c^2} \nabla T$$



Critical thermal gradient

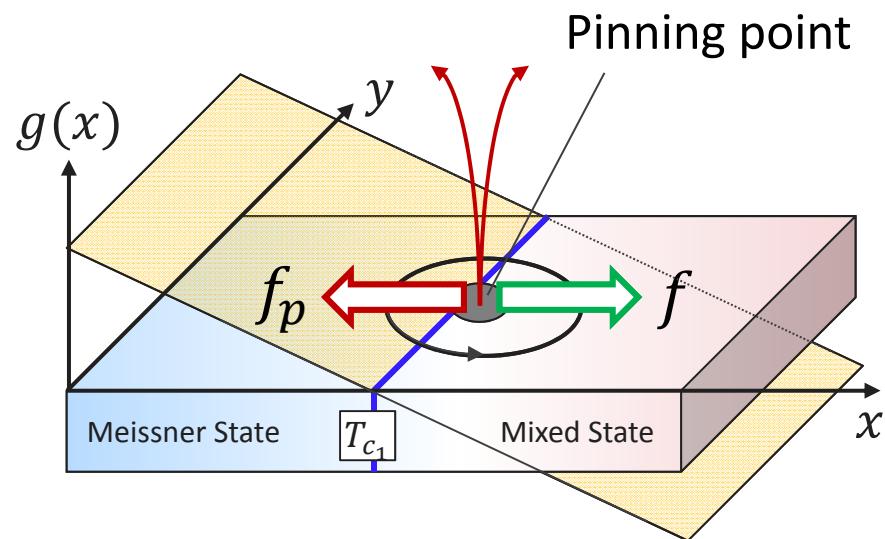
The *pinning force acting against the expulsion* is defined in terms of critical current density J_c :

$$f_p = |\bar{J}_c \times n\bar{\Phi}_0| = J_c B$$

The *minimum thermal gradient needed to expel vortices* is the critical thermal gradient ∇T_c :

$$\nabla T_c = \frac{J_c T_c^2}{2H_{c1}(0)T}$$

$$\nabla T_c \propto J_c \propto f_p$$



Statistical model for the expulsion ratio

Let's define a probability density function for flux expulsion:

→ the *probability of expelling vortices with the thermal gradient ∇T_{c_i} is $P(\nabla T_{c_i})$* , hence the expulsion ratio is:

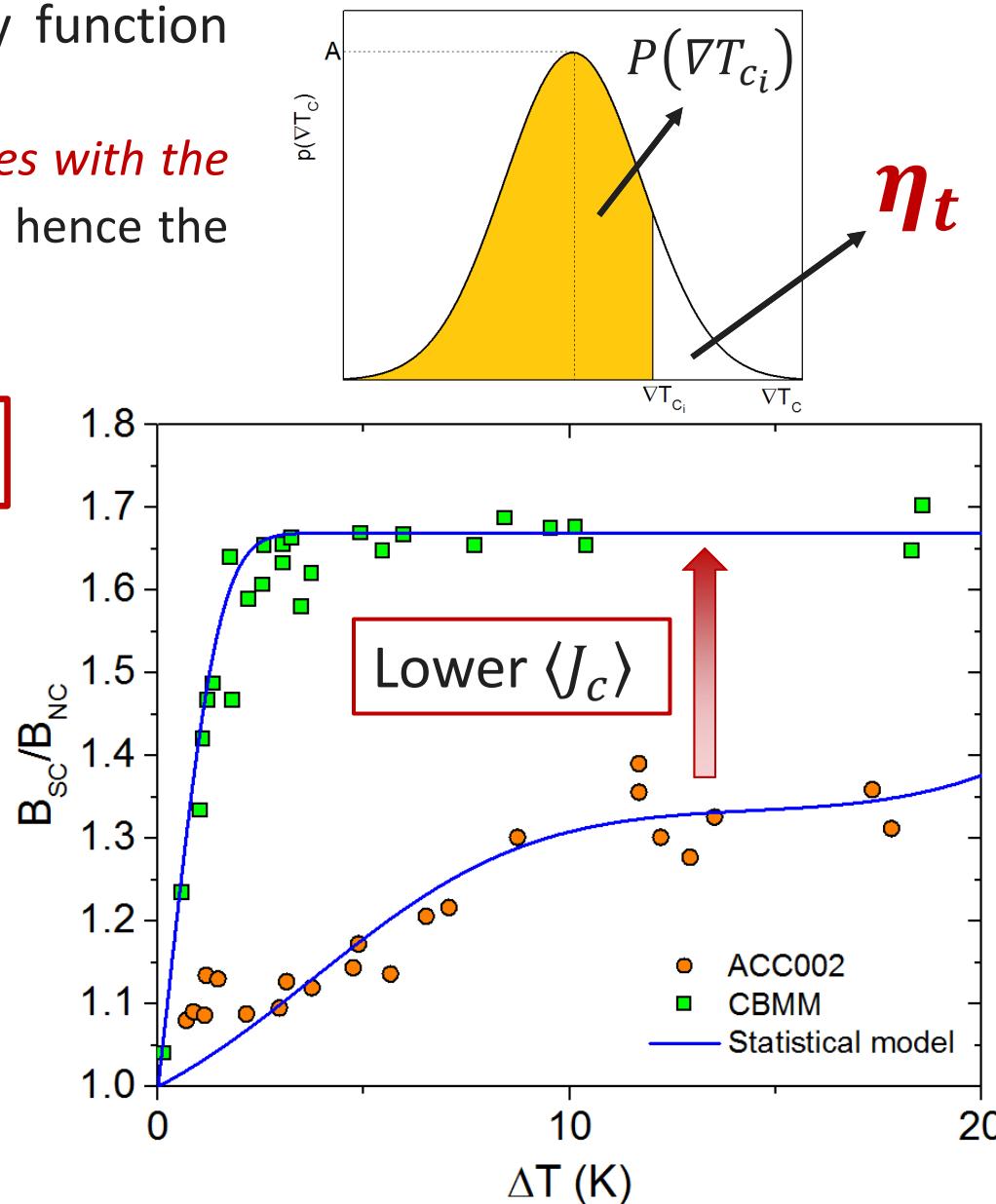
For TESLA shape

$$B_{SC}/B_{NC} = 1 + 0.74 \cdot P(\nabla T_{c_i})$$

The model predicts $\langle J_c \rangle$ in agreement with literature^{1,2}:

Cavity name	$\langle J_c \rangle$ (A/mm^2)
CBMM	0.3
ACC002	1.6

- M. Martinello, M. Checchin *et al.*, to be published
 Data: S. Posen *et al.*, J. Appl. Phys. **119**, 213903 (2016)
¹ G. Park *et al.*, Phys. Rev. Lett. **68**, 12 (1992)
² L. H. Allen and J. H. Claassen, Phys. Rev. B **39**, 4 (1989)



Vortex Viscosity, Pinning Force and Vortex Motion Equation

Viscosity against vortex motion

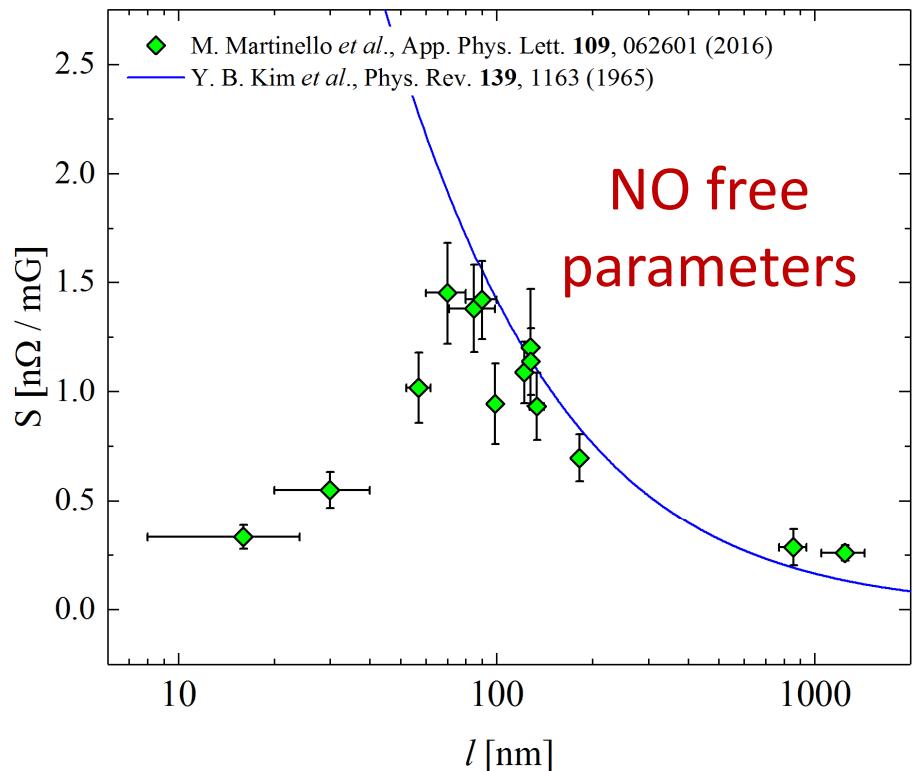
The resistivity in the flux-flow regime was defined by Kim *et al.*¹ as:

$$\rho_{flux-flow} = \frac{\Phi_0 B}{\eta}$$

Where η is the material viscosity against the vortex motion²:

$$\eta(l) = \frac{\Phi_0 B_{c2}(T)}{\rho_n(l)}$$

- $\rho_{flux-flow}$ describes the RF surface resistance for large mean-free-path.
- The low man-free-path region is not described:
 \Rightarrow *pinning plays a central role!*



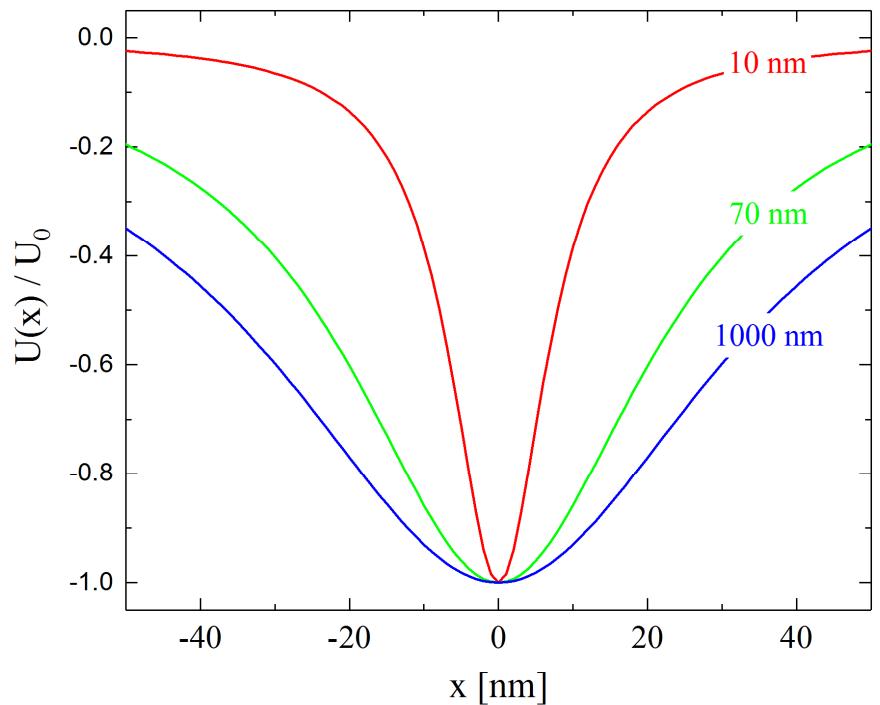
¹Y. B. Kim *et al.*, Phys. Rev. **139**, 1163 (1965)

²J. Bardeen and M. J. Stephen, Phys. Rev. **140**, 1197 (1965)

Qualitative dependence of pinning on the mean-free-path

- Pinning force: “interference” between the spatial variations of the order parameter Ψ due to vortex and pinning center (*free energy minimization*)
- *The characteristic variation length of Ψ is the coherence length ξ*
- ξ depends on the mean-free-path
→ The *pinning potential depends on the mean-free-path*

$$U(x, l) = -\frac{U_0 \xi(l)^2}{\xi(l)^2 + x^2}$$



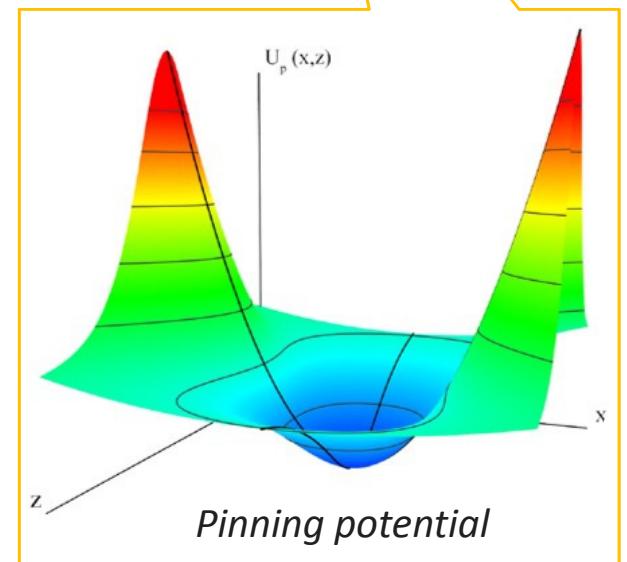
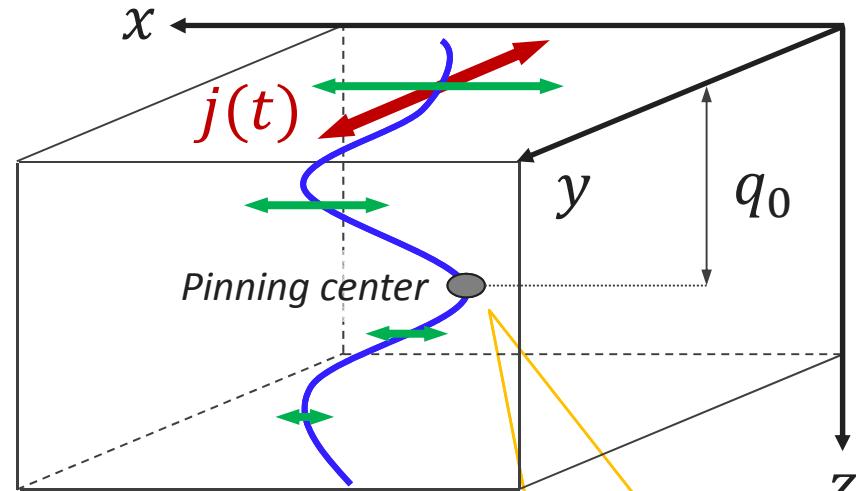
More realistic bi-dimensional pinning potential

- A *vortex* is a *mono-dimensional object* oscillating in the plane xz
- The *pinning center* is *localized at the depth q_0* from the RF surface
- The *pinning potential must be 2D:*

$$U_p(x, z) = -\frac{U_0 \xi^2}{\xi^2 + x^2 + (z - q_0)^2}$$

↓
Parabolic approx. along x

$$\approx -\frac{U_0 \xi^2}{\xi^2 + (z - q_0)^2} + \frac{U_0 \xi^2}{[\xi^2 + (z - q_0)^2]^2} x^2$$



Motion equation of a vortex

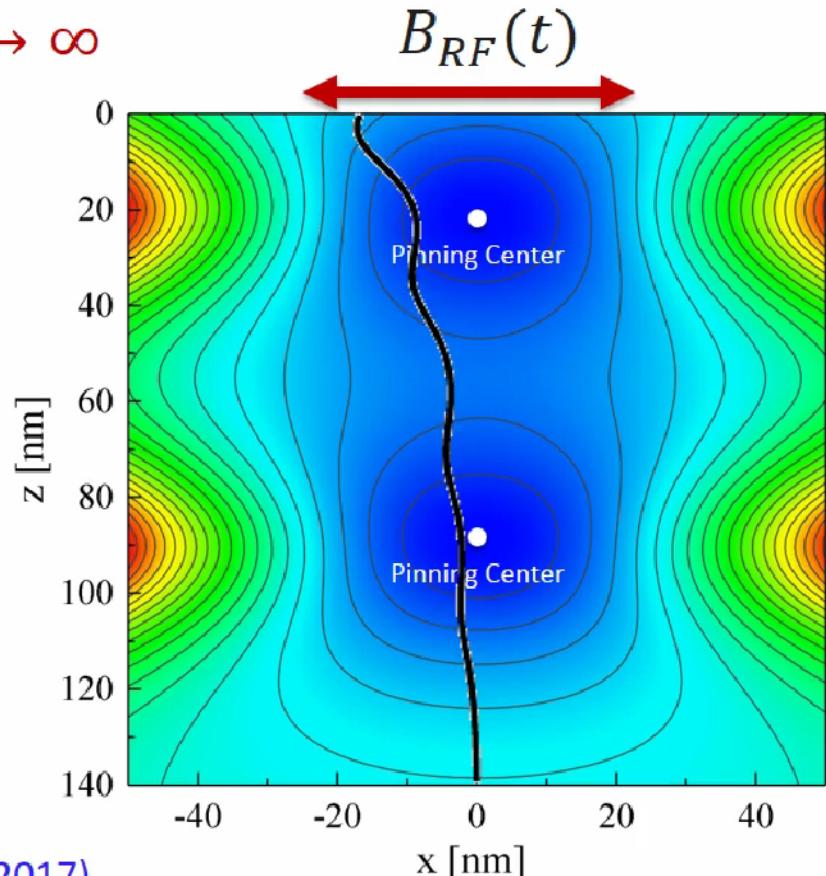
The motion equation has form:

$$M(l)\ddot{x} + \eta(l)\dot{x} + [p(z, l)x] = j_0\phi_0 \sin(\theta) e^{i\omega t - z/\lambda(l)}$$

2D pinning force!

The solution is valid from $z = 0$ to $z \rightarrow \infty$

- The pinning potential assumed is a 2D Lorentzian function
⇒ *parabolic approximation along x*
- The pinning constant $p(z, l)$ is depth-dependent
⇒ *flexible vortex line*
- Multiple pinning centers per flux line can be considered



Trapped Flux Sensitivity

—*S*—

Vortex surface impedance

The *complex resistivity* of the vortex line follows from the calculation of the apparent power (active plus reactive power) :

$$\rho(z, l) = \rho_1 + i\rho_2 = \frac{\phi_0^2 \sin^2(\theta)}{\pi \xi_0^2 [(p - M\omega^2)^2 + (\eta\omega)^2]} [\eta\omega + i(p - M\omega^2)]$$

The vortex surface impedance (using the classic definition of Z) is then:

$$Z(l) = \frac{\pi \xi_0^2 B}{\phi_0} \int_0^{q_0^\vee} \int_{U_{00}^\wedge}^{U_{00}^\vee} \cdots \int_0^{q_n^\vee} \int_{U_{0n}^\wedge}^{U_{0n}^\vee} \frac{\prod_{i=0}^n \Gamma(q_i) \Lambda(U_{0i})}{\int_0^L \frac{e^{-z/\lambda}}{\rho(z, l)} dz} dU_{00} dq_0 \cdots dU_{0n} dq_n$$

Number of vortices B/B_v

Vortex impedance weighted over normal distributions of pinning positions and strengths

Parameters affecting the sensitivity

The sensitivity S can be tuned acting on several parameters:

1. Mean free path— l
2. Frequency— f
3. Pinning center depth— q_0
4. Pinning center strength— U_0

1. Mean-free-path dependence

- Small l – pinning regime $\eta \ll p$:

$$\rho_1(l, U_0) \approx \frac{\eta(l)}{p(l, U_0)^2}$$

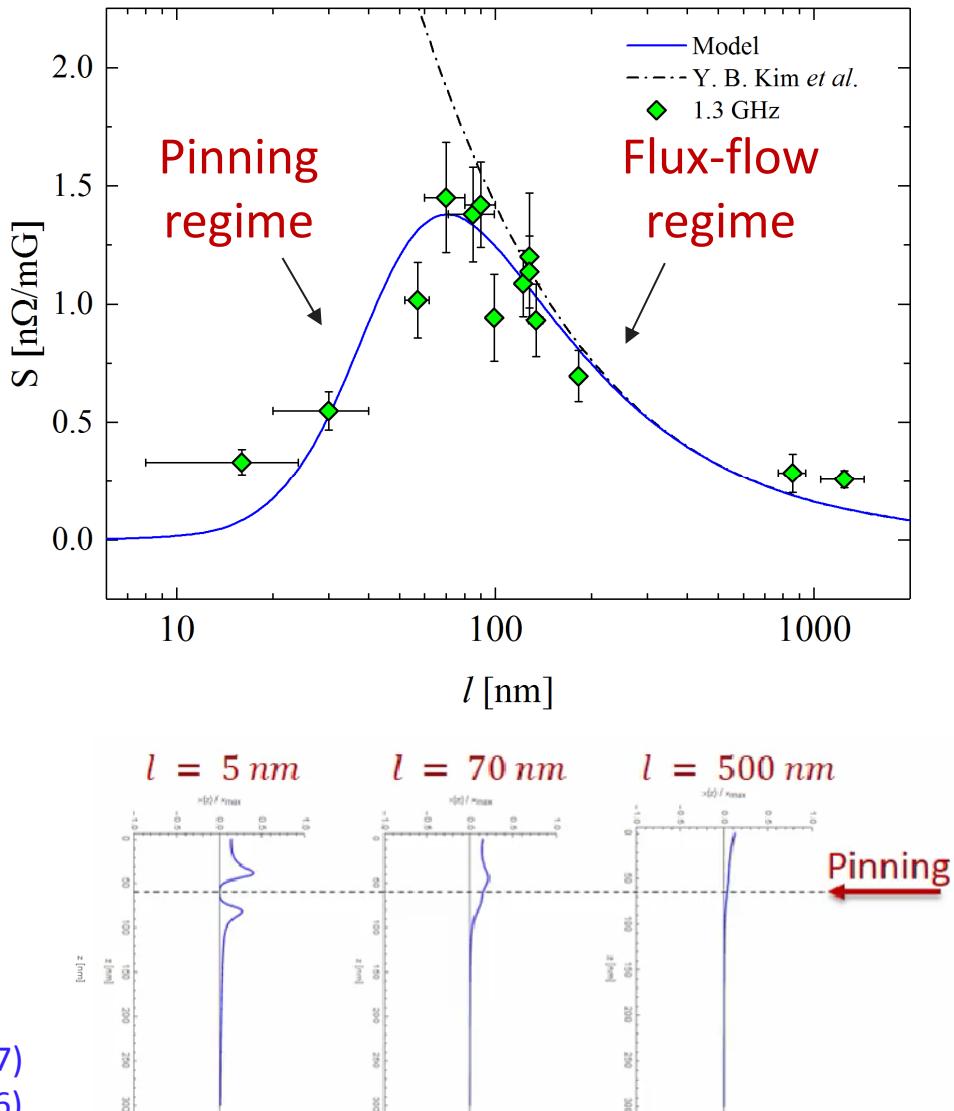
ρ_1 increases with l and ω^2 , decreases with the increasing of U_0

- Large l – flux-flow regime $\eta \gg p$:

$$\rho_1(l) \approx \frac{1}{\eta(l)}$$

ρ_1 decreases with l , independent on ω and U_0

M. Checchin *et al.*, Supercond. Sci. Technol. **30**, 034003 (2017)
 Data: M. Martinello *et al.*, App. Phys. Lett. **109**, 062601 (2016)



2. Frequency dependence

- Small l – *pinning regime* $\eta \ll p$:

$$\rho_1(\omega) \approx \omega^2$$

ρ_1 increases with ω^2

- Large l – *flux-flow regime* $\eta \gg p$:

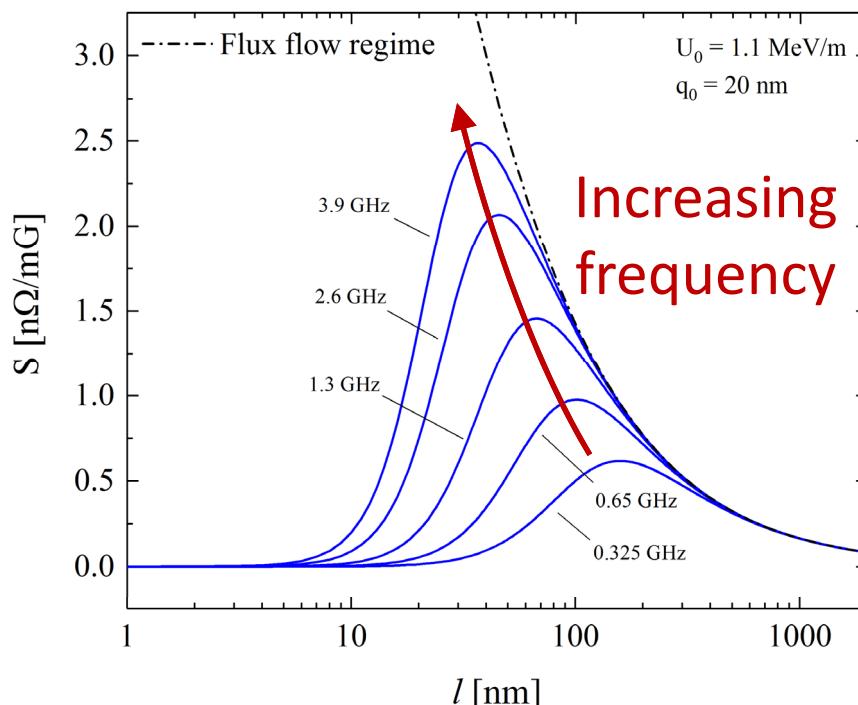
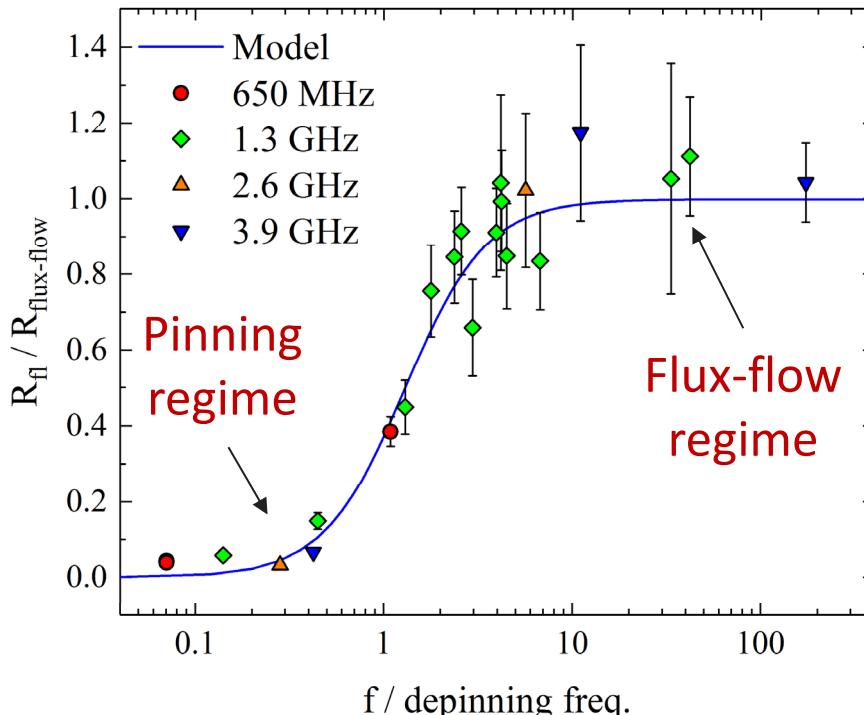
$$\rho_1 = \text{constant}$$

ρ_1 independent on ω

- The higher f the higher the sensitivity peak
- Lower frequencies* are favorable to *minimize the sensitivity*

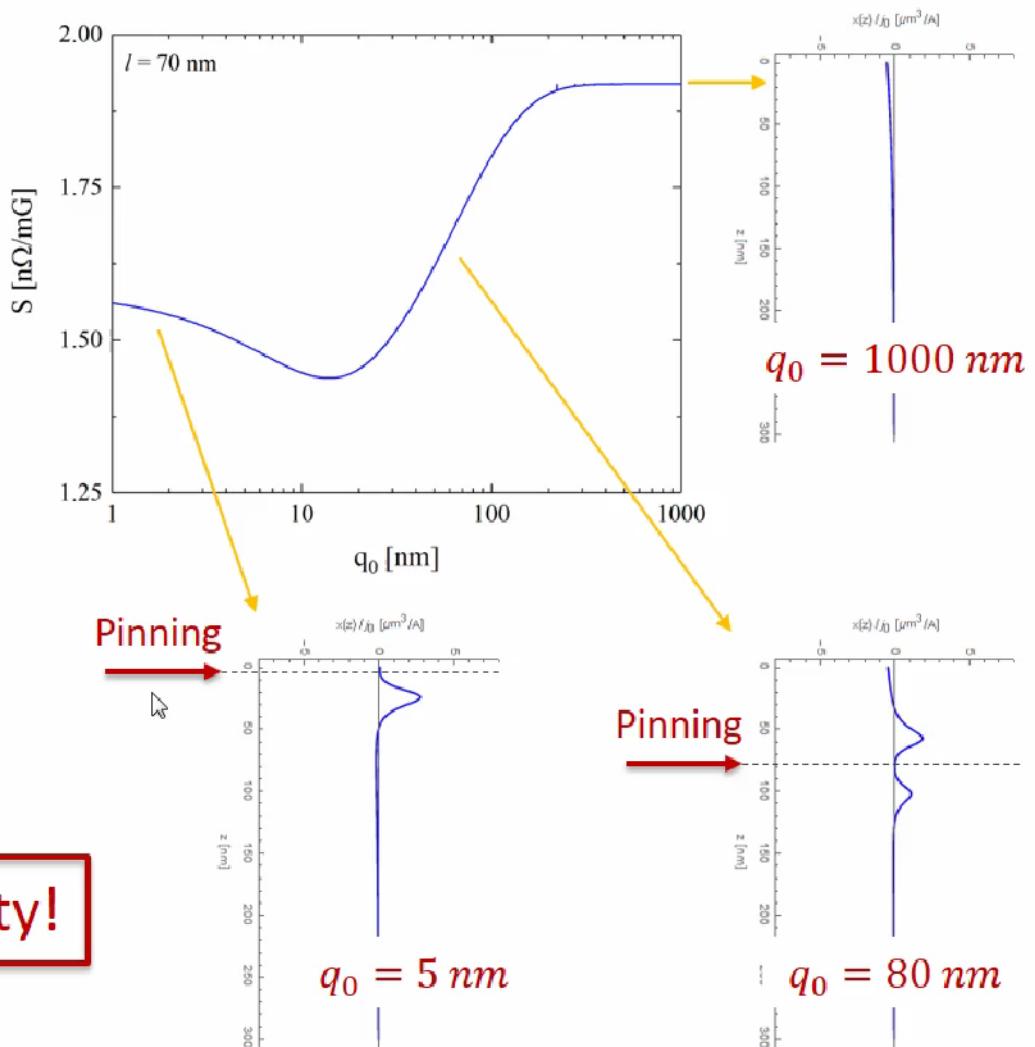
M. Checchin *et al.*, Supercond. Sci. Technol. **30**, 034003 (2017)

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3. Pinning center depth dependence

- The pinning site distance from the surface q_0 determines the resistance
- For instance, if $l = 70 \text{ nm}$:
 - $q_0 \cong 15 \text{ nm} \Rightarrow \text{sensitivity is the lowest}$
 - $q_0 > 400 \text{ nm} \Rightarrow \text{constant sensitivity}$
 - $\text{bulk pinning does not affect the vortex oscillation!}$

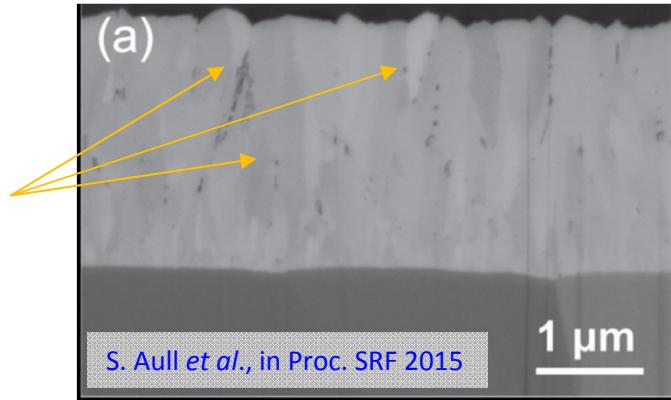


⇒ S is a near-surface property!

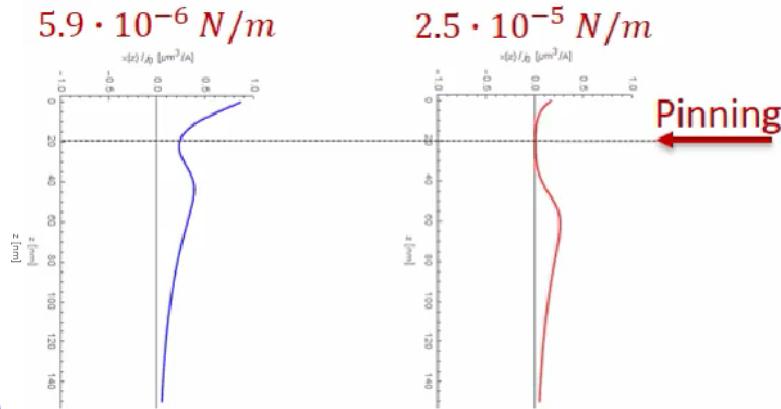
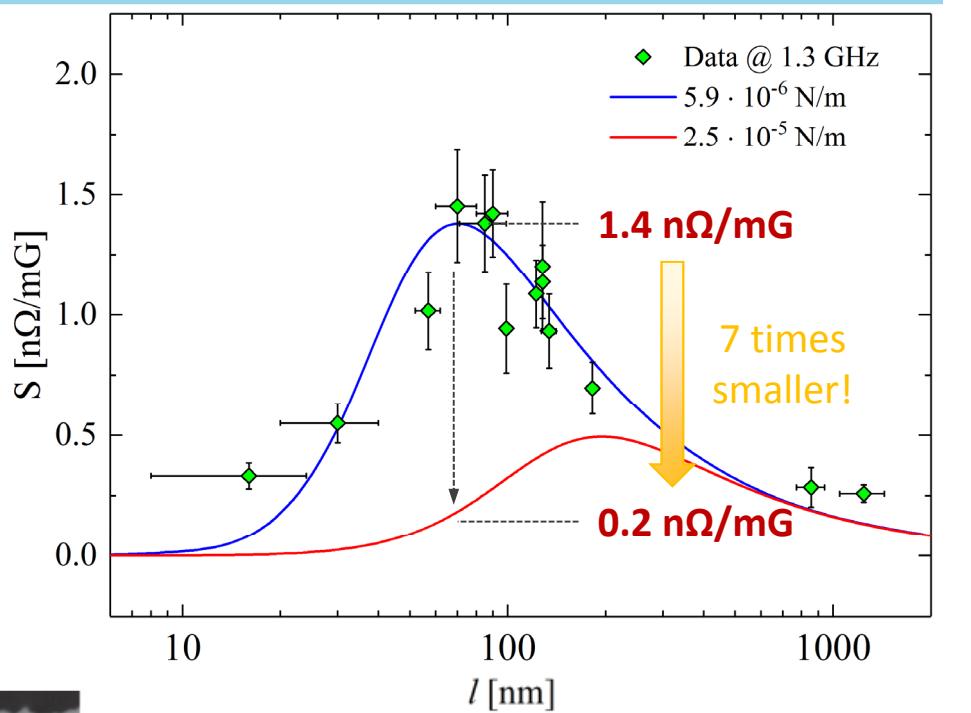
4. Pinning center strength dependence

- The *higher* the *pinning center strength*, the *higher* the *pinning force* and the *more constrained* the *oscillation*
- Dirtier or more defective materials (e.g. *sputtered Nb thin films*) have larger pinning strength

Porosities and defects in a Nb thin film enhance the pinning force



M. Checchin *et al.*, Supercond. Sci. Technol. **30**, 034003 (2017)



Conclusions

- Trapping Efficiency— $\eta_t(\nabla T, J_c)$ —bulk property:
 - Defined by the *balance of pinning and Gibbs free energy gradient* at the interface between Meissner and mixed state
 - Well described by a statistical argumentation
- Trapped Flux Sensitivity— $S(l, \omega, q_0, U_0)$ —near-surface property:
 - a. Two regimes of dissipation:
 - Small l : *pinning regime*, vortices constrained by pinning
 - S increases if $l \uparrow$, $\omega \uparrow$ and $U_0 \downarrow$
 - Large l : *flux-flow regime*, vortex motion counteracted by viscosity
 - S decreases if $l \uparrow$, but independent on ω and U_0
 - b. Pinning depth dependence:
 - Pinning site distance from the surface q_0 determines the resistance
 - *Bulk pinning does not affect the sensitivity*
 - c. Pinning strength dependence:
 - The larger U_0 , the smaller the sensitivity

Thank you for your attention



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